

**Amendments to the Claims:**

The listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

**1-12 (Cancelled).**

**13 (Currently Amended):** A method of forming a pattern on a reticle substrate, the method comprising:

modulating light directed to a first portion of a photosensitive layer using a plurality of tilted mirrors in a mirror array wherein each of the tilted mirrors are included as part of a piston displacement element so that a ~~[[the]]~~ combination of tilting of the mirrors and a ~~[[the]]~~ relative displacement of the mirrors combine to create varying degrees of interference of light waves on an ~~[[the]]~~ image, the amount of interference corresponding to a combination of a ~~[[the]]~~ degree of tilting and a ~~[[the]]~~ degree of displacement; and

modulating light directed to a second portion of a photosensitive layer using ~~[[a]]~~ the plurality of tilted mirrors in ~~[[a]]~~ the mirror array wherein each of the tilted mirrors are included as part of ~~[[a]]~~ the piston displacement element so that the combination of tilting of the mirrors and the relative displacement of the mirrors combine to create varying degrees of interference of light waves on the image, the amount of interference corresponding to a combination of the degree of tilting and the degree of displacement.

**14 (Currently Amended):** The method of forming a pattern on a reticle ~~reeticle~~ substrate as recited in claim 13, wherein the mirrors are controlled such that at least two adjacent mirrors generate a phase difference of about 520 degrees on a predetermined portion of the photosensitive layer.

**15-16 (Cancelled).**

**17 (Currently Amended):** The method of forming a pattern on a reticle ~~reetiele~~ substrate as recited in claim 13, wherein the individual mirrors are used to write a first feature of the pattern and wherein at least one of the mirrors are used to write a second feature of the pattern.

**18 (Currently Amended):** The method of forming a pattern on a reticle ~~reetiele~~ substrate as recited in claim 13, wherein a piston component of the mirrors is configured such that two adjacent mirrors exhibit about 180 degrees in phase difference.

**19-20. (Cancelled).**